

**Abstract of the Disclosure**

A process control system that controls processing executed on semiconductor wafers by processing apparatuses 120 , 122,124 installed in each bay (area) 110 inside a factory the processing results of which are predictable, having installed in the corresponding bay, at least one measuring apparatus 130 that executes a measuring operation on workpieces undergoing the processing in the bay, a transfer path 140 of a transfer apparatus, through which the workpieces are transferred among various apparatuses installed within the bay including the individual processing apparatuses and the measuring apparatus and a process control device 150 that controls the processing apparatuses, the measuring apparatus and the transfer apparatus in the bay. This structure reduces the length of time (cycle time) to elapse from the processing through the inspection operation and also improves the operating rate of each processing apparatus.